



INSITU PAT SENSOR TECHNOLOGY



Customized solutions for particle
measurement under process conditions for
R&D and pilot plants

Insitu PAT Sensor

***You are satisfied
with your measurement?
Let's talk about it!***



www.sequip.de



Content

Insitu PAT Sensor	3
Basics of technology	4
Product range	6
LSRA—Laser Scattering Radar Analyser	8
PMS— Particle Monitoring System	10
ECA— Emulsions Characteristic Analyser	11
LPS—Live Particle Sizer	12
IPAS— Insitu Particle Analysing System	13
IMAS— Insitu Morphology Analysing System	13
APAS— Advanced Particle Analysing System	14
PAT System	15
Sensor fitting	17
Measured Products	18
Our service for you	19
Contact	20



Insitu PAT sensors

The patent-registered PAT Sensor technology quantifies size and number of particles in originally concentrated dispersion based on the optic measurement of back reflection in connection with ToF (Time of Flight) technology. The influence of process parameters on the product will be identified fast and effectively. In contrast to normal particle analyzers PAT Sensors work with a *Self Selecting Focus* which guarantees the highest resolution of particles in the focal point.

Insitu PAT Sensors identify the particle size distribution of thinned and originally concentrated suspensions and emulsions as well as results of disperse present dry products. By the transparent signal analysis based on the newest developments of laser-based analysis technology by Sequip the operator is able to see his actual results under insitu conditions.

Size, the profile of the signal and the surface finish of the particle will be identified and analyzed to result in a real image of the particle system.

Advantages

- √ Based on facts statistical analysis because of more than 100.000 signal pictures
- √ Fitting of the sensor directly in reactor or in a pipeline possible
- √ No sample taken
- √ Insitu operation from petri dish up to beaker and reactor

Thereby:

- ⇒ Stability control under process conditions
- ⇒ Faster development of new formulas
- ⇒ Quality saving 24h a day

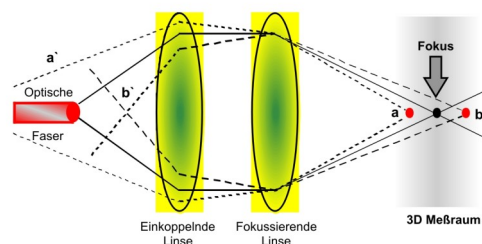


Basics of technology

Basis of success: ORM Technology

Patented ORM technology (Optical Back Reflection Measurement) allows an analysis of the whole particle system because of operation of selective working focus system.

In short the laser beam leaves the optical fibre (shown as a solid line). It passes through the coupling lens and the focussing lens, rejoins at the focal point scanning the sample in an elliptical orbit. If the light of the laser beam hits a particle or droplet at the focal point, the reflected light is then sent back to the optical fibre on the exact same path.



Moving of the focus into the medium:

1D -> static focus

2D -> circular moving focus

3D -> spiral vertical moving focus

An optical mechanical system conducts the laser beam spiraled. The patent-registered dynamic focus is synchronized and moved with higher speed into the medium to be measured. It is assured that the particles are only measured in the focus and the surrounding with the other particles is faded out.

Multiple scattering won't be registered because of the patent-registered opt mechanical design of the sensor.

The spiral dynamic focus in connection with the patent-registered opt mechanical technology is decisive advantage for the normal haze measurement and the Laser Scattering Radar Analyzer (LSRA) (see p.8).

The product to be measured has to be optical back-reflecting and have enough difference between trigger medium and product.



Basics of technology

Multi Capture Signal Analysis

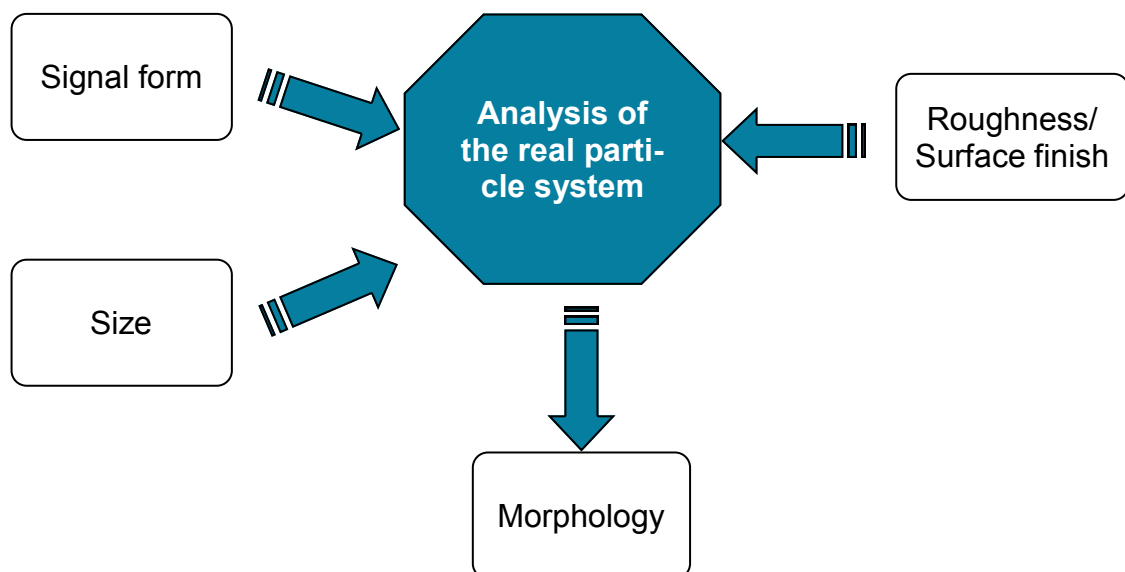
Based on the previously described patented 3D ORM technology Sequip developed **Multi Capture Signal analysis**.

The factor of the signal form and profile-dependent signals is captured and evaluated by a high performance electronic system. Information on the surface finish and profile of the particle are necessary to identify the real size and the change of profile.

All signal images will be saved in the Multi Capture Signal Analysis and are available to be evaluated by the electronic system.

This high-developed technology is applied by the systems IPAS (Insitu Particle Analyzing System), IMAS (Insitu Morphology Analyzing System) and APAS (Advanced Particle Analyzing System) by Sequip.

Advantages





Product range

Modular customer-oriented product control with Insitu particle analysis

LSRA—Laser Scattering Radar Analyser

Utilization: Product control and improvement

Displays of fingerprints – changes inside the particle system are detected.
Function: extended laser measurements with optical back reflection

PMS—Particle Monitoring System

Utilization: Process control and improvement,
10-<300µm, 30-<600µm

Control in definitely adjusted size range of the particle systems under production conditions.
Function: 1D ORM technology

ECA—Emulsion Characteristic Analyser

Utilization: measurement of drop size in emulsions and slurry,
0.5 – 125µm

Undiluted measurements in laboratory and insitu process in real-time.
Function: 3D ORM technology

PAT Sensor

Utilization: insitu Particle analysis with different metering ranges,
2-2000µm

Undiluted measurements in laboratory and insitu process of dispersed phase systems in real-time.
Function: 3D ORM with a moving depth selective focus

Basic
Advanced
Highly Developed



Product range

Real particle through multi capture analysis

IPAS—Insitu Particle Analysing System

Utilization: Collection and analysis of signal forms to define morphologically crystals and particles; 0.5-2000µm

Undiluted measurements in highest concentration in laboratory and insitu process in real time, dispersion of the signal form.
Function: deep, variable and selective focus with integrated signal form analysis

IMAS—Insitu Morphology Analysing System

Utilization: insitu particle analysis in dynamic measurement range, crystallization and polymerization processes, identification of product specification and form inhomogeneity; 0.5-2000µm

Undiluted measurements in highest concentration in laboratory and insitu process in real time.
Function: Multi Capture Signal Analysis plus identification of geometrical signal form functions and roughness and size of crystals and particles.

APAS—Advanced Particle Analysing System

Utilization: insitu particle analysis with dynamic measurement range and analysis of form signals—open signal tap by an oscilloscope exit for research applications
0,5—4000 µm

Undiluted measurements in pumpable concentration in laboratory and insitu process in real time.
Function: Multi Capture Signal Analysis plus identification of geometrical form factors, roughness and size of crystals and particles with open signal structure.

High- End
Advanced Technology



Laser Scattering Radar Analyser

The principle

To capture the homogeneity of products an analysis electronic systems seizes and counts different particle sizes which produce different multi scattering effects, and sorts them in different length categories by their signal length.

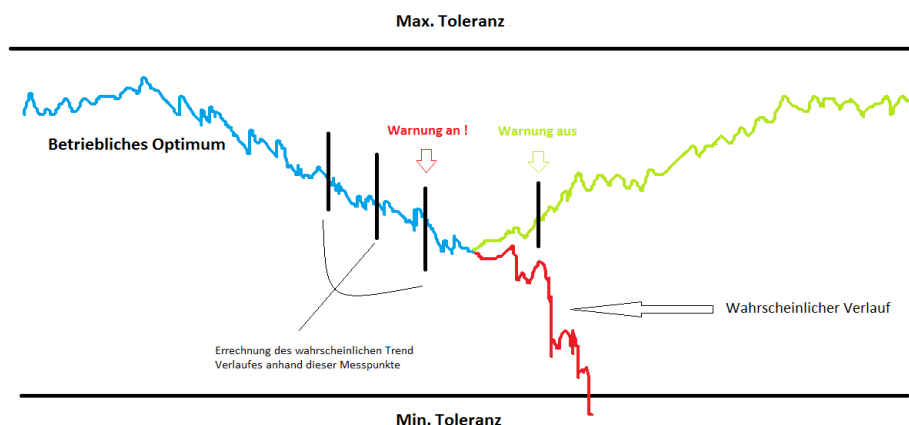
The signals are capture by a wide, launched angle and a lens system inside the sensor and presented as a signal length distribution. This distribution of all signal length during a period of time is an advanced signal distribution of the Multi Scattering range. The signals proportional to the size are captured and presented from a particulate system of disperse phase systems, which develop under process conditions because of the Multi Scattering effects.

The raw data is saved and can be relayed to the Process Control System of the operator.

Applied characteristics

On the basis of previously set tolerances for the “fingerprint” of the measured product you can influence and control the quality of the process.

The system calculates the characteristics of the current trend. If it is possible that the limit of the tolerance is over traveled, the unit will alarm the operator and calculate the time until the frontier crossing. If the trend changes, the alarm is deactivated and the process keeps running (see diagram).





Laser Scattering Radar Analyser

Application-benefits for the operator

- Optimized control and capture of crystallization processes, capture of the starting point of germination and control of the fine and roughness fraction rates by optical density allocation and detecting of the limit point of crystallization.
- PAT control as a fingerprint of batch and continuous processes to constant product quality
- Control of automatically sampling to reduce time in laboratory
- Capture of agglomeration and deagglomeration processes

Benefits for the operator by sensor technology

- No rotating lens system inside the sensor, therefore you have maintenance rates of 5 years
- Design of the medium-touching parts according to customer's specification, for example C 276
- Polymer-free seal system therefore prevention to crystallization inside the seal chamber
- Norm sensor diameters of 14, 18, 25 mm and mini plant sensors
- Sensor length of 150 up to 4000 mm therefore even existing reactors can be equipped through manhole
- Sensor pressure range: Vacuum up to 16 bar
- Medium temperature: -40° to +165°C
- Optional extension regarding the application conditions for OEM customers possible
- Best price/ gain proportion
- Multivendor-capability, cost-efficient installation by the customer!



Process control:
365 Days / 24Hours

*Sleep well, the sensor is
working for you!*

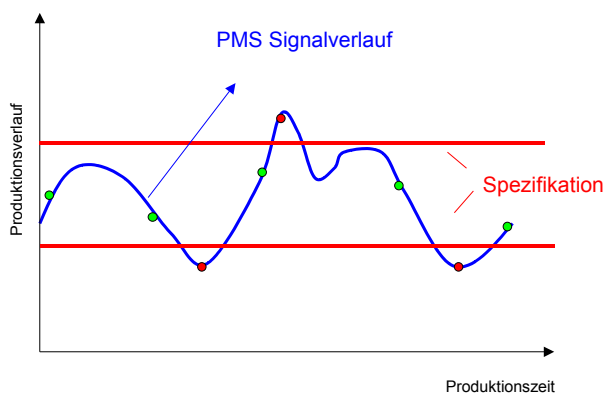


PMS

Particle Monitoring System

The principle

To control continuously a defined fraction of a particle distribution a one-dimensional selective focus captures all particles which are in the focus with a factory-provided narrow static size-range.



Particle size parameters are controlled continuously in line, in real time and 24h. Sampling are made, when the PMS sensor collect irregularities. Therewith, the laboratory released from controlling the samples which are in the specific range.

Technical Datas

Measurement range:	<10 –300 μm and < 30 – 600 μm
Concentration:	< 40 %
Temperature:	-120° up to 220 °C
Pressure:	Up to 16 bar
Sensors:	18 mm, 24 mm

Options possible !

Application range:

Suspensions:

E.g. aluminum oxide, sulphur (polymers) , water-based varnish, lactose, glucose, sugar, calcium chloride precipitation crystals, microcapsule, potassium chloride

Dry products:

E.g. cement, pigments

Organic products:

E.g. organic flocculating, putrid slimes, fermentations, vitamin flocculating, yeasts, insulin, carotene, brewer's yeasts





ECA

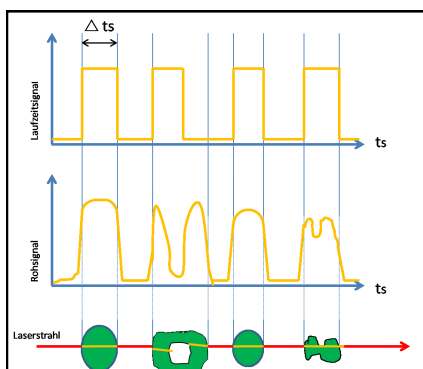
Emulsion Characteristic Analyser

The principle

The ECA sensor is used to analyze drop sizes in original concentrated emulsions. The ECA sensor technology is based on the Time of Flight (ToF) technology and the optical back reflection measurements (ORM). A high-energy laser beam scans with 10mW the dispersed particles and drops and their structure. The beam captures their geometric extension, when they cross it in the dynamic selective focus. The recorded times in microsecond range are displayed as a distribution.

Utilization:

The ECA sensor enables to measure the change in size in original formulations of suspensions and emulsions, when you have insitu conditions with minimum distance of 1µsec to the next measurement between to drops.



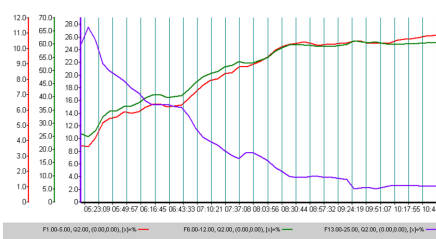
Graphic display of the signal formation

Technical data

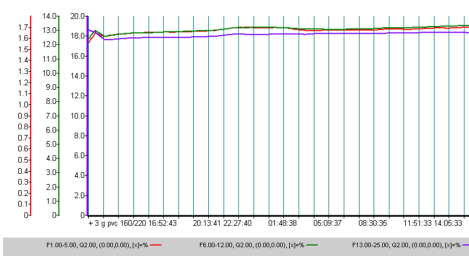
Measurement range:	>0,5 – <60 µm and < 2 – <125 µm
Concentration:	< 70 % - 80% (Oil/Water)
Temperature:	5° - 85 °C
Pressure:	Up to 6 bar
Sensors:	18 mm

Interpretation with the WIN ORM—Software

Example of an instable emulsion



Example of a stabile emulsion



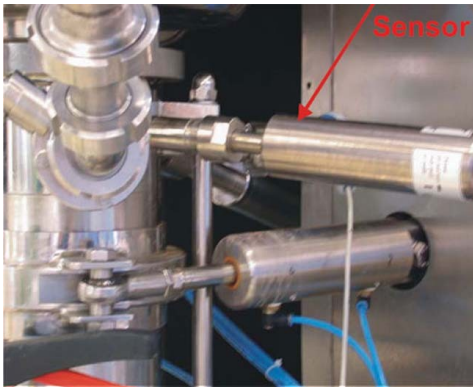


ECA

Emulsion Characteristic Analyser

Watch with the ECA-Sensor :

Agglomeration of material systems,
Stability of dispersphased systems
Dissolution process of substances



Inline Fitting between mixer and homogenisation



Sensor in undiluted emulsion

Advantages for user:

- No sample taken
- Development of new products in shorter time
- Real results because of measuring in original concentration
- Sensor is sterilisable—not working
- Continuously measurement 24h / 365 days a year



Live Particle Sizer PAT SENSORS

The principle

The sensors are used to analyze suspensions and their systems in wider size spectra to have easier laboratory application additional to the common laser diffraction.

The insitu PAT sensors use the patent-registered 3D ORM technology with its ToF method as a basis. A focused laser beam moves circular above a particle flow. The size is defined by the period of time that is necessary to scan the focused particles. The sum of the data is used to create a statistical firm distribution.

The special kind of the selective 3D ORM measuring room and the combination with a electronically evaluation of the back reflection pulse are the particular characteristic of the 3D ORM technology.

In the statistical evaluation are just particles that are directly in the focus. Particles and drops outside the focus are excluded from the statistical evaluation by the patented optic.

Technical Data

Measurement range:	0,5 – 125 μm 1 – 500 μm 2 – 1000 μm 10 – 2000 μm
Concentration:	< 60 %
Temperature:	-20° up to 165 °C
Pressure:	Up to 16 bar
Sensor:	18 mm, 24 mm



Application range:

- ✓ Insitu process control and R&D laboratory
- ✓ Optimization and control of crystallization processes
- ✓ Control of polymerization processes
- ✓ Dynamic dispersion of disperse phase systems in original concentration
- ✓ Drop and particle system dispersion in suspensions and emulsions
- ✓ ATEX Version available

www.sequip.de



PAT Systems

Insitu Particle Analysing System—IPAS

The principle

Based on the ToF technology of the PAT sensors (cf. page 12) the focus is moved circular and also vertically into the particle flow.

By the signal tracing the dynamical and selective measurement range is aligned automatically for the crystal and particle sizes in the range of <0.5 up to $2000\text{ }\mu\text{m}$.

Technical Data

Measurement range	0,5 – 2000 μm
Concentration:	< 70 % - 80%
Temperature:	-90° to 220 °C
Pressure:	Vakuum up to 16; 32; 64 or 300 bar
Sensor:	14 mm; 18 mm; 25 mm; 30 mm; 45 mm



Insitu Morphology Analysing System—IMAS

The principle

Additional to the IPAS system also signal factors are captured and signals dependent on the form are evaluated by high performance electronic system. Information on the finish and the size of particles and crystals are prepared for a real particle image.

The evaluation is made by the Multi Capture Signal Analysis. All form signals are saved and available for the evaluation.

The open signal system is based on a high performance laser system. Surface structures are capture as a signal form, presented and saved in which particle pitches of $1\text{ }\mu\text{sec}$ are detected.



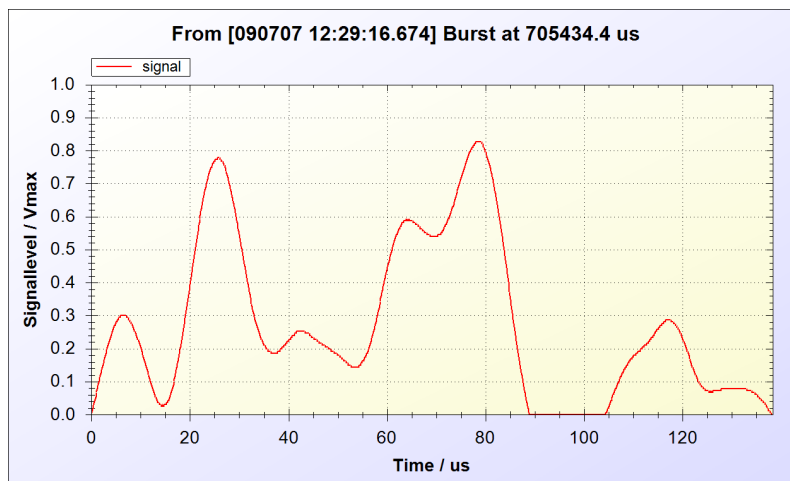
PAT Systems

APAS - Advanced Particle Analysing System

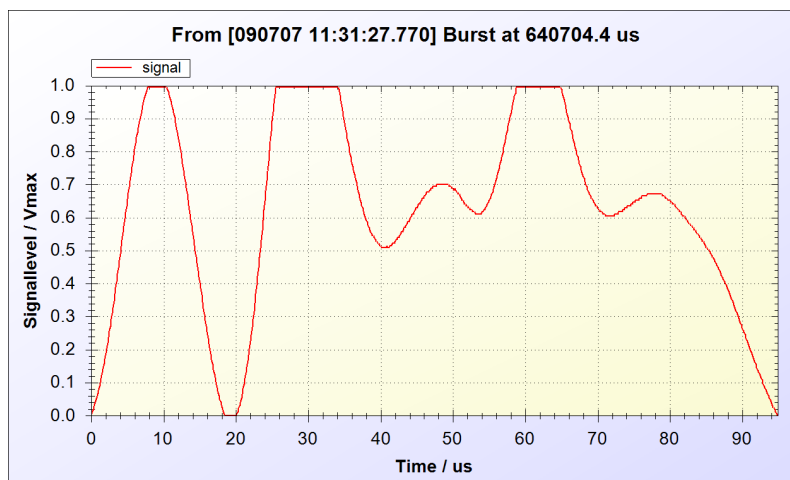
The principle

Sequip offers the APAS for basic research in universities and research institutes. The technology is based on the already commented ToF method and the Multi Capture Signal Analysis.

The decisive advantage is the possibility to grip raw signals by an oscilloscope exit. Therefore it is possible to research and explain conclusions of the particle signal development.



Evaluation of the Multi Capture Signal Analysis

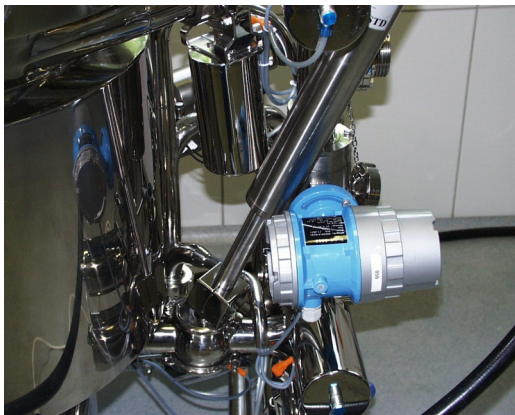




PAT Systems

Advantages for the user

- ⇒ Insitu stability control in production without sample taken and pump
- ⇒ In production control in real time
- ⇒ Online quality control with reducing lab analysis
- ⇒ Optimisation of solid matter quality and product cleanness
- ⇒ Formulation of new products in shorter time
- ⇒ Quality saving 24h / 365 days a year



Benefit

- ⇒ Modular systems reg. customer specification
- ⇒ Dynamic measurement ranges
- ⇒ Very low and very high temperature range
- ⇒ ATEX available
- ⇒ Working in high pressure and concentration ranges
- ⇒ Comfortable analysing software
- ⇒ Statistically results—based on facts





Measured products

Examples of products from 20 years of particle measurement

Aluminum oxide	Coffee concentrates	Polymer granules
Solution of washing powder	Cocoa	Polymer crystals
Eye drops	Cocoa butter	Polystyrene
Skin cream for babies	Potassium chloride	Polyvinyl chloride (PVC)
Beta-carotene	Lime milk	Porcelain slurry
Brewer's yeasts	Caramel	Pulp
Organic flakes	Cat litter	Powder lacquer
Organic ointment	Ceramic slurries <5µm	PVC emulsion
Epsomite	Ketoglucolic acid	PVC suspension
Bitumen emulsion	Ketchup sauces	Shaving foam
Butter	Silica gel	Plaster rock
Calcium chloride precipitation crystals	Silica gel 2 – 250 µm	Activated sludge
Antiperspirant cream	Sludge (s)	Salad creams and dressings
Dextrose	Carbon slurry after milling	Salt
Dextrose monohydrate	Crystals in emulsions <125 µm	Foam dissolution
Diamond slurry	Coolant emulsions	Chocolate
Emulsion paint	Copper ore <125 µm	Bruised grain granules
Print colors	Copper ore slurry	Sulfur crystals
Print colors paste	Lactose	Shampoo
Fertilizers	Lactose precipitation	Silver pigment paste
Iron ore slurry	Lactose powder	Silicone emulsions
Emulsions of microcapsules	LPG liquid	Soda
Antifoam	Air bubbles in diet oil	Sorbic acid
Pigments	Air bubbles in LPG	Steel / water in counter flow
Putrid slimes	Magnesium chloride precipitation crystals	Coating color with additives
Fermentations	Malt products with form identification	Styrene
Commercial sauce	Margarine	Disperse phase
Emulsions of fruits	MDF shavings	Ink
Fruit juice concentrate	Flour	Titanium dioxide
Animal feed	Multicomponent emulsions	Titanium dioxide in emulsions
Gas bubbles in margarine	Molasses	Tomato juice
Gas bubbles in Mouse au Chocolat	Metal powder	Toner slurry
Gas bubbles in vegetable fat	Metal powder suspensions	Over plus sludge
Grain	MgCl ₂ × 6 H ₂ O	Uranium particles
Medical plaster	Micro capsules	Vitamine flakes
Precipitation of plaster	Milk 1.5 and 3.5 % fat	Wax emulsions
Glass powder	Natural cosmetics	Washing base
Glucose	Kidney stone	Washing lotion
Gold colliery waste	Orange juice	Washing powder
Granules	NIVEA cream	Water-based varnish
Hair tinting lotion	Breadcrumbs	Fluidization granules
Ground meat /mincemeat /sausage meat	Paper fiber	Toothpaste
Hand lotion	Paper additives	Cellulose
Skin lotion with pigments	PCC	Cellulose slurry
Yeasts	Peeling lotion	Cement <45µm
High speed granulation	Penaten cream	Cinnamon
Chipped wood	Pentaerythritol	Sugar crystals
Hosta form powder	Seeds	
Immunization sugar <150 µm	Phosgene crystals	
Inert gas distribution in oil	Phosphate gravel 100 – 800 µm	
Yoghurt	Photo emulsions	
Insulin	Casein paint	
Coffee	Polyethylene (PE)	
Coffee extracts	Polymers and antifoams	



Our Service for you

Our service:

- + **Guidance round about solutions for your particle measurement**
We offer consulting by phone or individually face to face about suitable systems for particle measurement before purchase decision.
- + **Measurement with your samples**
You will send your samples to our laboratory and we measure them with the suitable system and send the results to you.
- + **Rental systems**
If you need our system only for a special task—Rent a particle measurement system and solve your problem reasonable!
- + **Consulting with our personal and our system at your company**
If you have a particle measurement problem? Our specialist will guide you and measure with our system at yours.

Reference customer

Shell;
Fraunhofer Institut Physikalische Prozesstechnik;
Siemens;
BASF;
Universität Cottbus;
Weleda;
TU Wismar



A special thank on this place to our partner and customer, which give us suggestions and feed back. Every discussion and every request brought us considerably closer to improve our technic.

We also thank to universities, which use our technology for Master- and doctoral dissertation. These insights gained are integrated in our research and technology work.

Because : more than hundred thousand of particle measurement systems are available and also many different solutions: We have one of them!

Contact

S&E—Sensor & Equipment GmbH
SEQUIP

Mrs. Elke Rüter
Sales Consultant
Angermunder Str. 22
D-40489 Düsseldorf
Germany

Tel.: ++49 (0)203 / 742140
Fax: ++49 (0)203 / 7421444
Email: rueter@sequip.de
www.sequip.de
www.sequip-rent-a-particle.com

More Products:

Image analysis system for lab wet and dry:
500 Nano, Flow-Cell, Zephyr
Vacuum dispersion for powder

Insitu image analysis: PIA (Particle Image Analyser)

Powdershape and Microshape

We like to send you more information!
Please do not hesitate to contact us!